# NANOCHEM® CleanCorr™ Hydrogen Fluoride Gas Purifiers

Removal of moisture and metals from Hydrogen Fluoride

NANOCHEM® CleanCorr™ Purifiers are designed to remove moisture and metals from hydrogen fluoride.

#### **Applications**

Hydrogen Fluoride purification for Chemical Vapor Deposition (CVD) wafer surface cleaning and etch process, where moisture and metals can affect the quality and purity of the wafer.

Hydrogen Fluoride purification for chamber cleaning where impurities such as moisture and metals can cause corrosion and contamination.

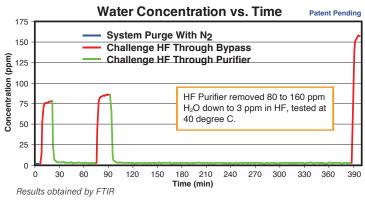
#### **Features and Benefits**

- Custom-designed adsorbent material for point-of-use moisture and metals removal offering:
  - High Capacity
  - Long Lifetimes
  - < 3 ppm Efficiency for moisture and metals in hydrogen fluoride
- Low Overall Cost of Ownership
- Room temperature operation no power required
- Easy to install and operate

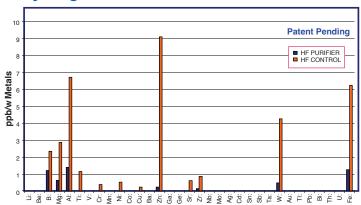
### **Specifications**

- 0.003 µm particle filter
- Internal surface finish < 10 μin Ra</li>
- Metal parts of Stainless Steel, Type 316L
- Maximum operating temperature of 40°C (104°F)

## Removal of H<sub>2</sub>O from Hydrogen Fluoride



### **Hydrogen Fluoride Purifier Metals Results**



Analyzed by ICP-MS for metals concentrations (ppbw)

### **Purifier Models / Sizes**

NANOCHEM® CleanCorr™ purification medium is available in the following hardware configurations for point-of-use applications:

	Maximum Recommended Flow Rate		Media Volume	Maximum Allowable Operating Pressure	
Model	slpm	(NM³/hr)	ml or liters	psig	(Mpa)
Purifilter®	3	(0.2)	25 ml	1,000	(7)
A-Series	15-50	(0.9)	60-500 ml	500	(3.55)
WK-Series*	10-150	(9)	50-500 ml	500-1000	(3.55)

NOTE: 0.003 µm particle filter standard on all models.

\*Three-valve manifold with isolation and bypass valves allows disconnection of purifier without interrupting process gas flow for WK-75, WK-300, WK-500

